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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/772,736	02/05/2004	Juan-Jann Jou	24061.80 (TSMC2003-0343)	5636
42717 7590 03/20/2007 HAYNES AND BOONE, LLP 901 MAIN STREET, SUITE 3100			EXAMINER	
			NGUYEN, THANH T	
DALLAS, TX	/3202		ART UNIT	PAPER NUMBER
			2813	
SHORTENED STATUTOR	RY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
3 MO	ONTHS	03/20/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

	Application No.	Applicant(s)
	10/772,736	JOU ET AL.
Office Action Summary	Examiner	Art Unit
	Thanh T. Nguyen	2813
The MAILING DATE of this communic	<u> </u>	
A SHORTENED STATUTORY PERIOD FOR WHICHEVER IS LONGER, FROM THE MA - Extensions of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this communing of the provision of the provision of after SIX (6) MONTHS from the mailing date of this communing of the provision of the	ILING DATE OF THIS COMMUNIC 37 CFR 1.136(a). In no event, however, may a re- nication. tory period will apply and will expire SIX (6) MONT ill, by statute, cause the application to become ABA	ATION. ply be timely filed HS from the mailing date of this communication. NDONED (35 U.S.C. § 133).
Status		
Responsive to communication(s) filed This action is FINAL . 2b Since this application is in condition for closed in accordance with the practice	o)☐ This action is non-final. or allowance except for formal matte	• •
Disposition of Claims		
4)	withdrawn from consideration. on and/or election requirement. Examiner. a) accepted or b) objected to b	
Replacement drawing sheet(s) including the	ne correction is required if the drawing(s	s) is objected to. See 37 CFR 1.121(d).
11) The oath or declaration is objected to be Priority under 35 U.S.C. § 119	by the examiner. Note the attached	Office Action of form PTO-152.
12) Acknowledgment is made of a claim fo a) All b) Some * c) None of: 1. Certified copies of the priority do 2. Certified copies of the priority do 3. Copies of the certified copies of application from the Internationa * See the attached detailed Office action	ocuments have been received. Ocuments have been received in Ap I the priority documents have been real Bureau (PCT Rule 17.2(a)).	plication No eceived in this National Stage
Attachment(s)	_	
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date 	D-948) Paper No(s).	mmary (PTO-413) /Mail Date ormal Patent Application -·

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DETAILED ACTION

Response to Arguments

Applicant's arguments filed 12/29/06 have been fully considered but they are not persuasive.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

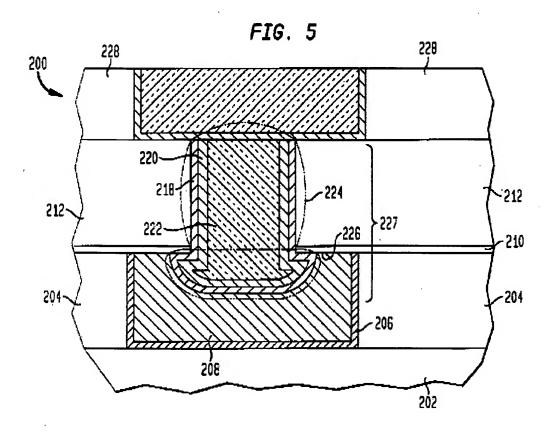
Claims 27, 31-32, 36, 39-41, 45, 46, 49 are stand rejected under 35 U.S.C. 102(e) as being anticipated by Barth et al. (U.S. Patent No. 6,613,664), previously applied.

Referring to figures 4-5, 8, Barth et al. teach an interconnect structure, comprising:

- a first conductive layer (208) located in a substrate (202/204);
- a dielectric layer (210/212) overlying the first conductive layer (208) and having an opening (213) extending to the first conductive layer (208); and

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a second conductive layer (218/220/222) located in the opening (213) and contacting a portion of the first conductive layer (208), wherein an interface between the first and second conductive layers substantially conforms to a substantially curvilinear profile (see figure 5 for detail).



Regarding to claim 31, 45, diffusion barrier layer (218) interposing the dielectric layer and the second conductive layer (see figure 5).

Regarding to claim 32, 46, diffusion barrier layer (218) interposing the first and second conductive layer and substantially conforming to the interface profile (see figure 5).

Regarding to claims 36, 49, wherein the interface profile is substantially concave relative to the substrate (see figure 5).

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Regarding to claim 39, wherein the opening is one of a via hole opening and a dual damascene opening (see figure 8).

Regarding to claim 40, wherein at least one of the first and second conductive layers comprises one of copper and a copper alloy (see col. 5, lines 47-50, col. 6, lines 43-45).

Regarding to claim 41, an integrated circuit device, comprising:

a plurality of semiconductor devices coupled to a substrate (see figures 3-6, and col. 5, lines 27-30); and

an interconnect structure (208/222) coupling ones of the plurality of semiconductor devices, the interconnect structure (see figures 5) including:

a plurality of first conductive layers (208);

a dielectric layer (210/212) overlying ones of the plurality of first conductive layers (208) and having a plurality of openings (213) each extending to one of the plurality of first conductive layers (see figures 5/8); and

a plurality of second conductive layers (222) located in ones of the plurality of openings (213) and each contacting a portion of one of the plurality of first conductive layers (208), wherein each interface between corresponding ones of the first and second conductive layers substantially conforms to a substantially curvilinear profile (see figure 5/8).

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 33, 38, 47, 51 are stand rejected under 35 U.S.C. 103(a) as being unpatentable over Barth et al. (U.S. Patent No. 6,613,664) as applied to claims 27, 31-32, 36, 39-41, 45, 46, 49 above in view of Straight et al. (U.S. Patent No. 5,567,650), previously applied.

Barth et al. teaches an interconnection structure above. However, the reference does not teach the interface of the profile is a substantially W-shaped, or substantially trapezoidal, peaked profile.

Straight et al. teaches forming an interconnect structure wherein the interface profile is substantially W-shaped (see figure 6).

Therefore, it would have been obvious to one of ordinary skill in the art to form the W-shaped trench in process of Barth et al. as taught by Straight et al. because it would form a desired shape of interconnect structure. It is well settled that, the change in shape of the trench (i.e. W-shaped, or substantially trapezoidal, peaked profile) was a matter of design choice which a person of ordinary skill in the art would have found obvious absent persuasive evidence that the particular configuration of the trench was significant. *In re Dailey*, 357 F.2d 669, 149 USPTO 47 (CCPA 1996).

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Claims 28-30, 34-35, 37, 42-44, 48, 50 are stand rejected under 35 U.S.C. 103(a) as being unpatentable over Barth et al. (U.S. Patent No. 6,613,664) as applied to claims 27, 31-32, 36, 39-41, 45, 46, 49 above in view of ordinary skill in the art, previously applied.

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Barth et al. teaches an interconnection structure above. However, the reference does not teach the specific depth/height range of the profile of claims 28-30, 34-35, 37, 42-44, 48, and 50.

The specific range of depth/height of the profile in claims 28-30, 34-35, 37, 42-44, 48, and 50 are considered to involve routine optimization while has been held to be within the level of ordinary skill in the art. As noted in In re Aller, the selection of reaction parameters such as temperature and concentration would have been obvious:

"Normally, it is to be expected that a change in temperature, or in concentration, or in both, would be an unpatentable modification. Under some circumstances, however, changes such as these may impart patentability to a process if the particular ranges claimed produce a new and unexpected result which is different in kind and not merely degree from the results of the prior art...such ranges are termed critical ranges and the applicant has the burden of proving such criticality.... More particularly, where the general conditions of a claim are disclosed in the prior art, it is not inventive to discover the optimum or workable ranges by routine experimentation."

In re Aller 105 USPQ233, 255 (CCPA 1955). See also In re Waite 77 USPQ 586 (CCPA 1948); In re Scherl 70 USPQ 204 (CCPA 1946); In re Irmscher 66 USPQ 314 (CCPA 1945); In re Norman 66 USPQ 308 (CCPA 1945); In re Swenson 56 USPQ 372 (CCPA 1942); In re Sola 25 USPO 433 (CCPA 1935); In re Dreyfus 24 USPO 52 (CCPA 1934).

Therefore, one of ordinary skill in the requisite art at the time the invention was made would have used any range suitable to the device of an interconnect structure of Barth et al. in order to optimize the process and produce the interconnect structure desired to the parameters desired..

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It would have been obvious to a person of ordinary skill in the requisite art at the time of the invention was made to optimize the profile height/depth range, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. In re Aller, 105 USPQ 233 (CCPA 1955).

Response to Arguments

Applicant's arguments filed 12/29/06 have been fully considered but they are not persuasive.

In view of the argument, rejection under 35 U.S.C 102 (b) in view of Straight et al., claims 27, 33, 36, 40-41, 47, and 49 is withdrawn.

Applicant contends that conductive lines (208) are not located in a substrate (202). In response to applicant that this is not found persuasive because Barth clearly teaches conductive lines (208) are located in substrate (202/204, It is noted that substrate is anything that use as a base to support another structure or layer). The claim does not specify the material of the substrate. Therefore, substrate includes layers 202 and 204 with the first conductive layer (208) located within the substrate (202/204) and dielectric layer (210/212) formed on the first conductive layer (208) with the opening in the dielectric layer (210/212), forming a second conductive layer (218/220/222) with the interface between the first conductive layer (208) located in a substrate (202/204) and a second conductive layer (218/220/222) located in the opening and contacting a portion of the first conductive layer (208, noted that layer 208 contacting layer 218, the interface also between these two layers).

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thanh Nguyen whose telephone number is (571) 272-1695, or by Email via address Thanh.Nguyen@uspto.gov. The examiner can normally be reached on Monday-Thursday from 6:00AM to 3:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr., can be reached on (571) 272-1702. The fax phone number for this Group is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR

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system, see http://pairdirect.uspto.gov. Should you have questions on access to thy Private PAIR system, contact the Electronic Business center (EBC) at 866-217-9197 (toll-free).

Thanh Nguyen Patent Examiner

Patent Examining Group 2800

TTN